



Express Mail No. ER452509568US *IFW*
Attorney Docket No.: AM-8893

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF: Ki-Ho Baik et al.

SERIAL NO.: 10/817,140

FILED: April 2, 2004

FOR: METHOD OF IMPROVING THE UNIFORMITY
OF A PATTERNED PHOTORESIST ON A MASK

§ GROUP ART UNIT: Unknown
§
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§ EXAMINER: Unknown
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§ Attorney Docket No.:
§ AM-8893

Date: June 23, 2004

INFORMATION DISCLOSURE STATEMENT
TRANSMITTAL LETTER

Hon. Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450

Sir:

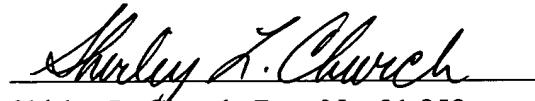
Applicants are submitting the subject Information Disclosure Statement under 37 CFR § 1.97(b)(1). This Information Disclosure Statement is being submitted within three (3) months of the filing date of the subject application.



CERTIFICATE OF MAILING UNDER 37 CFR § 1.10

I hereby certify that this paper is being deposited with the U.S. Postal Service on the date shown below with sufficient postage as U.S. EXPRESS MAIL NO. ER452509568US in an envelope addressed to: Mail Stop DD, Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

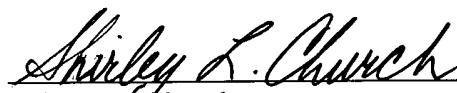
Date: June 23, 2004


Shirley L. Church, Reg. No. 31,858

Applicants do not believe that any fee is due in connection with the filing of this Information Disclosure Statement under 37 CFR § 1.97(b)(1). However, in the event that any additional fee is due, the Commissioner is hereby authorized to charge Deposit Account No. 50-1512 of Shirley L. Church, Sunnyvale, California, in the amount of such fee.

This transmittal letter is submitted in duplicate for accounting purposes.

Respectfully submitted,



Shirley L. Church
Registration No. 31,858
Attorney for Applicants

Correspondence Address:
Patent Counsel
Applied Materials, Inc.
P.O. Box 450-A
Santa Clara, California 95052



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INFORMATION DISCLOSURE STATEMENT
UNDER 37 CFR § 1.97(b)(1)

**Hon. Commissioner for Patents
P.O. Box 1450
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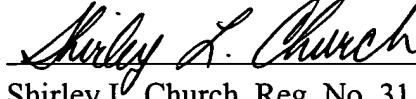
Sir:

In accordance with 37 CFR § 1.97(b)(1), applicants hereby request consideration of this Information Disclosure Statement. This Information Disclosure Statement is being submitted within three (3) months of the filing date of the subject application. Applicants are providing herewith a copy of each document cited on the attached Form PTO-1449.

CERTIFICATE OF MAILING UNDER 37 CFR § 1.10

I hereby certify that this paper is being deposited with the U.S. Postal Service on the date shown below with sufficient postage as U.S. EXPRESS MAIL NO. ER452509568US in an envelope addressed to: Mail Stop DD, Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450

Date: June 23, 2004

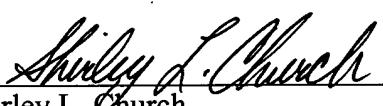


Shirley L. Church, Reg. No. 31,858

The submission of this Information Disclosure Statement and Form PTO-1449 is not an admission that the art cited is "prior art" with respect to the present invention, nor is it a representation that no better art exists. Applicants hereby reserve the right to swear behind or otherwise disprove any alleged "prior" nature of any art cited should the facts support and the situation warrant such an action.

If the Examiner has any questions, s/he is respectfully requested to contact the undersigned attorney at the telephone number set forth below.

Respectfully submitted,



Shirley L. Church
Registration No. 31,858
Attorney for Applicants
(650) 473-9700

Correspondence Address:
Patent Counsel
Applied Materials, Inc.
P.O. Box 450-A
Santa Clara, California 95052



FORM PTO-1449
(Equivalent)

U.S. Department of Commerce
Patent and Trademark Office

U.S. Application Serial No.
10/817,140

Atty. Docket No.
AM-8893

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(Use several sheets if necessary)

Ki-Ho Baik et al.
Applicants

April 2, 2004
Filing Date

U. S. PATENT DOCUMENTS

<u>Examiner Initial</u>	<u>Document Number</u>	<u>Issue Date</u>	<u>Name</u>	<u>Class</u>	<u>Subclass</u>	<u>Filing Date If Appropriate</u>
	4,102,683	07/25/78	DiPiazza	96	38.4	
	5,554,485	09/10/96	Dichiara et al.	430	271.1	
	5,723,237	03/03/98	Kobayashi et al.	430	30	
	5,879,853	03/09/99	Azuma	430	166	
	5,879,863	03/09/99	Azuma et al.	430	322	
	5,935,768	08/10/99	Biche et al.	430	401	
	6,048,672	04/11/00	Cameron et al.	430	327	
	6,703,169	03/09/04	Fuller et al.	430	5	

U. S. PATENT APPLICATION DOCUMENTS

<u>Examiner Initial</u>	<u>Document Number</u>	<u>Publication Date</u>	<u>Name</u>	<u>Class</u>	<u>Subclass</u>	<u>Filing Date</u>
	2002/0012876 A1	01/31/02	Angelopoulos et al.	430	271.1	08/17/01
	2002/0182514 A1	12/05/02	Montgomery et al.	430	5	05/03/01

Examiner Date Considered

Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

FOREIGN PATENT DOCUMENTS

<u>Examiner Initial</u>	<u>Document Number</u>	<u>Publication Date</u>	<u>Name</u>	<u>Class</u>	<u>Subclass</u>	<u>Translation (If Appropriate)</u>
	EP 0987600	03/22/00	Adams et al.	G03F	7/09	
	EP 0989460	03/29/00	Shimomura et al.	G03F	7/004	
	JP 10048831	02/20/98	Sony Corp.	G03F	007/11	Abstract

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

____ G. Amblard et al., "Diffusion Phenomenon and Loss of Adhesion in Chemically Amplified Negative Resists", *Microelectronic Engineering*, 17, pp. 275-278 (1992).

____ P. Buck et al., "Performance of the ALTA® 3500 scanned-laser mask lithography system", *Proceedings of the SPIE Conference on Photomask and X-Ray Mask Technology V*, Kawasaki, Japan, SPIE Vol. 3412, pp. 67-78 (April 1998).

____ K. Katoh et al., "Improvement of Post Exposure Delay Stability of Chemically Amplified Positive Resist", *Proceedings of the SPIE Symposium on Photomask and X-Ray Mask Technology VI*, Yokohama, Japan, SPIE Vol. 3748, pp. 62-68 (Sept 1999).

____ K. Kemp et al., "Effects of DUV Resist Sensitivities on Lithographic Process Window", *SPIE*, Vol. 3049, pp. 955-962 (1997).

____ C. A. Mack et al., "Matching Simulation and Experiment for Chemically Amplified Resists", *Proceedings of the SPIE Conference on Optical Microlithography XII*, SPIE Vol. 3679, pp.183-192 (March 1999).

____ Z. Masnyj et al., "Evaluation of Negative DUV Resist UVN30 for Electron Beam Exposure of NGL Masks", *SPIE*, Vol. 3997, pp. 525-529 (2000).

____ U. Okoroanyanwu et al., "Impact of Optical Absorption on Process Control for Sub-0.15- μ m Device Patterning Using 193-nm Lithography", *SPIE*, Vol. 3998, pp.781-790 (2000).

____ C. P. Soo et al., "Enhancement or Reduction of Catalytic Dissolution Reaction in Chemically Amplified Resists by Substrate Contaminants", *IEEE Transactions on Semiconductor Manufacturing*, Vol. 12, No. 4, pp. 462-469 (Nov 1999).

____ M. Zuniga et al., "Application of a General Reaction/Diffusion Resist Model to Emerging Materials with Extension to Non-Actinic Exposure", *SPIE*, Vol. 3049, pp. 256-268 (1997).

Examiner	Date Considered
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Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.
